Special Issue

Advances in Plasma Diagnostics and Applications

Message from the Guest Editors

The aim of this Special Issue is to collect original research and review articles on the most recent plasma applications and to diagnose their processes, to elucidate the characteristics of plasma and mechanisms of plasma-induced processes. Potential topics include, but are not limited to:

- Experimental measurement methods and diagnostic tools for detection of radicals in gas and liquid phase
- Modification in materials
- Materials processing (deposition, etching, washing, etc.)
- Industrial applications including water purification
- Biomedical/Agricultural/Food processing applications

Guest Editors

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Deadline for manuscript submissions

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Message from the Editor-in-Chief

You are invited to contribute either a research article or a comprehensive review for consideration and publication in *Processes* (ISSN 2227-9717). *Processes* is published in open access format – research articles, reviews, and other content are released on the internet immediately after acceptance. The scientific community and the general public have unlimited, free access to the content. As an open access journal, *Processes* is supported by the authors and their institutes through the payment of article processing charges (APCs) for accepted papers. We would be pleased to welcome you as one of our authors.

Editor-in-Chief

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